The Fabrication of mixed halide perovskite ($CH_3NH_3PbI_{3-x}CI_x$) solar cells by single step coatingwithout annealing process

 $\begin{array}{c}
\begin{array}{c}
\begin{array}{c}
1,2, & 3,2,*, & 1,2\\
\end{array} \\
\begin{array}{c}
\end{array}; ^{2} Functional Crystallization (FCC);\\ 3\\
(imromy@khu.ac.kr^{*})
\end{array}$

The mixed halide perovskite (CH₃NH₃Pbl_{3-x}Cl_x) is used for highly efficient photovoltaic material because of its improved charge transport property and diffusion length by CI doping without band gap change. The one-step method is the most simplest coating method to form perovskite thin-films by using of one-solution which dissolvinged methyl ammonium iodide and lead chloride in solvent. However, if mixed halide perovskite is fabricated with one-step method, it should be annealed long time (about 40 min at 100) to obtain pure perovskite layer with elimination of excess MAI (methyl ammonium iodide) and CI in one-step solution. This perovskite layer cannot cover substrate enough because it agglomerates itself by annealing process. Consequentially, it brings poor morphology of perovskite layer. So we tried to form mixed halide perovskite thin -films without remove annealing process through one -step method.